

10-17-00

152

Filed Via Express Mail

Rec. No.: E1522395272US

On: OCTOBER 16, 2000

By:

LINDA E. HASTINGS

Any fee due as a result of this paper, not covered by an
enclosed check, may be charged on Deposit Acct. No. 08-
1634.

Attorney Docket No.:NEKW14.868



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor: KAICHIRO NAKANO, ET AL.

Serial No.: 09/036,219

Filed: March 6, 1998

Title: **CHEMICALLY AMPLIFIED RESIST LARGE IN
TRANSPARENCY AND SENSITIVITY TO EXPOSURE
LIGHT LESS THAN 248 NANOMETER WAVELENGTH
AND PROCESS OF FORMING MASK**

Examiner: J. Chu

Group Art Unit: 1752

October 16, 2000

152-1700 MAIL ROOM
OCT 20 2000

Assistant Commissioner for Patents
BOX NON-FEE AMENDMENT
Washington, D.C. 20231

RECEIVED

RESPONSE TO OFFICE ACTION

SIR:

In response to the Office Action dated August 9, 2000, the period for responding thereto having been set to expire on November 9, 2000, please consider the following: